

| L Number | Hits | Search Text | DB | Time stamp |
|----------|---------|---|---|---------------------|
| 1 | 2482 | (430/311).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 15:10 |
| 2 | 344 | ((430/311).CCLS.) and ((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 15:17 |
| 3 | 106 | ((430/311).CCLS.) and ((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 15:17 |
| 4 | 1473 | (430/322).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 15:17 |
| 5 | 197 | ((430/322).CCLS.) and ((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 15:17 |
| 6 | 77 | ((430/322).CCLS.) and ((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 15:18 |
| - | 1 | 09/683929 | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/22 16:52 |
| - | 6369 | (430/5).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/22 16:52 |
| - | 69151 | ((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 15:11 |
| - | 1078592 | (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 15:11 |
| - | 18431 | ((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/22 17:57 |
| - | 7354 | ((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4))) and (mask or photomask or reticle) and (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/22 17:59 |

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|---|-------|---|---|---------------------|
| - | 187 | (((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and ((Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4)))) and (mask or photomask or reticle) and (resist or photoresist)) and ((430/5).CCLS.) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/22 18:07 |
| - | 6 | "6472107" | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/22 18:08 |
| - | 23616 | (Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 08:47 |
| - | 246 | 430/296.ccls. and ((Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 10:13 |
| - | 166 | (430/296.ccls. and ((Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask)))) and (Cr or chrom\$4 or W or tungsten or Ta or tantalum) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 09:43 |
| - | 80 | (430/296.ccls. and ((Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask)))) not ((430/296.ccls. and ((Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask)))) and (Cr or chrom\$4 or W or tungsten or Ta or tantalum)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 09:43 |
| - | 73 | ((430/296.ccls. and ((Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask)))) and (Cr or chrom\$4 or W or tungsten or Ta or tantalum)) and (charg\$4 or discharg\$4) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/11/23 10:24 |